Supporting Information

Programmable Nanoengineering Templates for Fabrication of

Three-Dimensional Nanophotonic Structures

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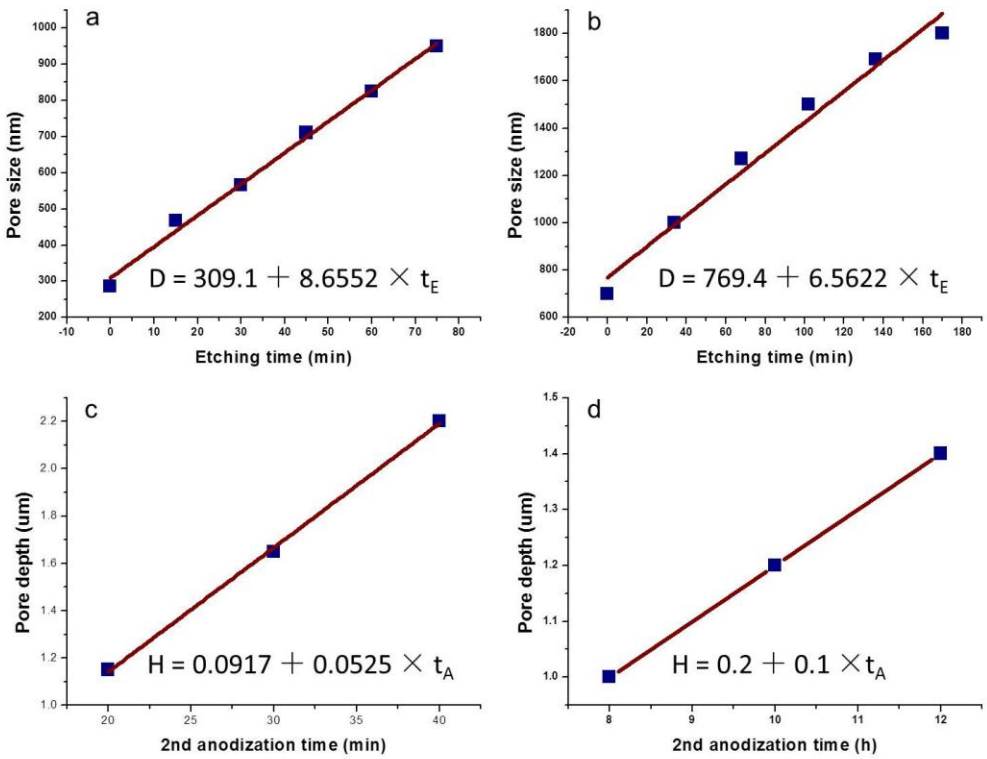

Figure S1. Pore size as a function of wet etching time in 5 wt% H_3PO_4 at 53 ^oC for a) 1 μm pitch and b) 2 μm pitch AAM. Pore depth as a function of 2^{nd} anodization time for c) 1 μm pitch and d) 2 μm pitch AAM.

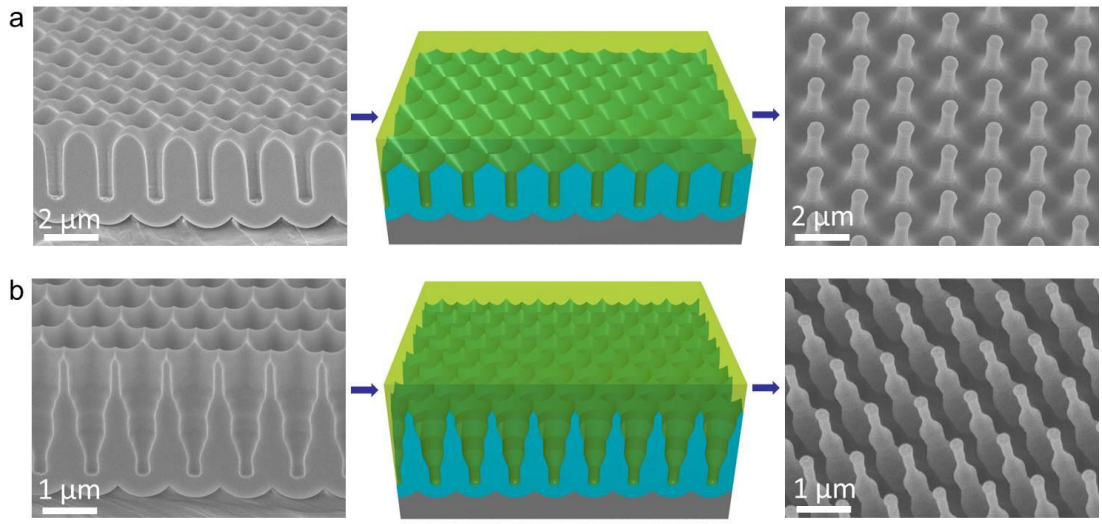

Figure S2. Thermal press process to template a) PC nanopillars and b) PC nanotowers.

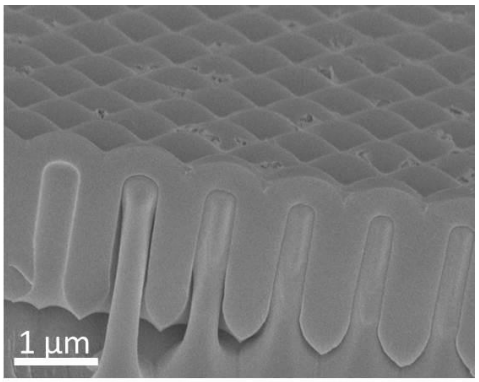

Figure S3. Cross-sectional view SEM image of PI nanopillars, showing that the beads on top of them are formed during peeling process.

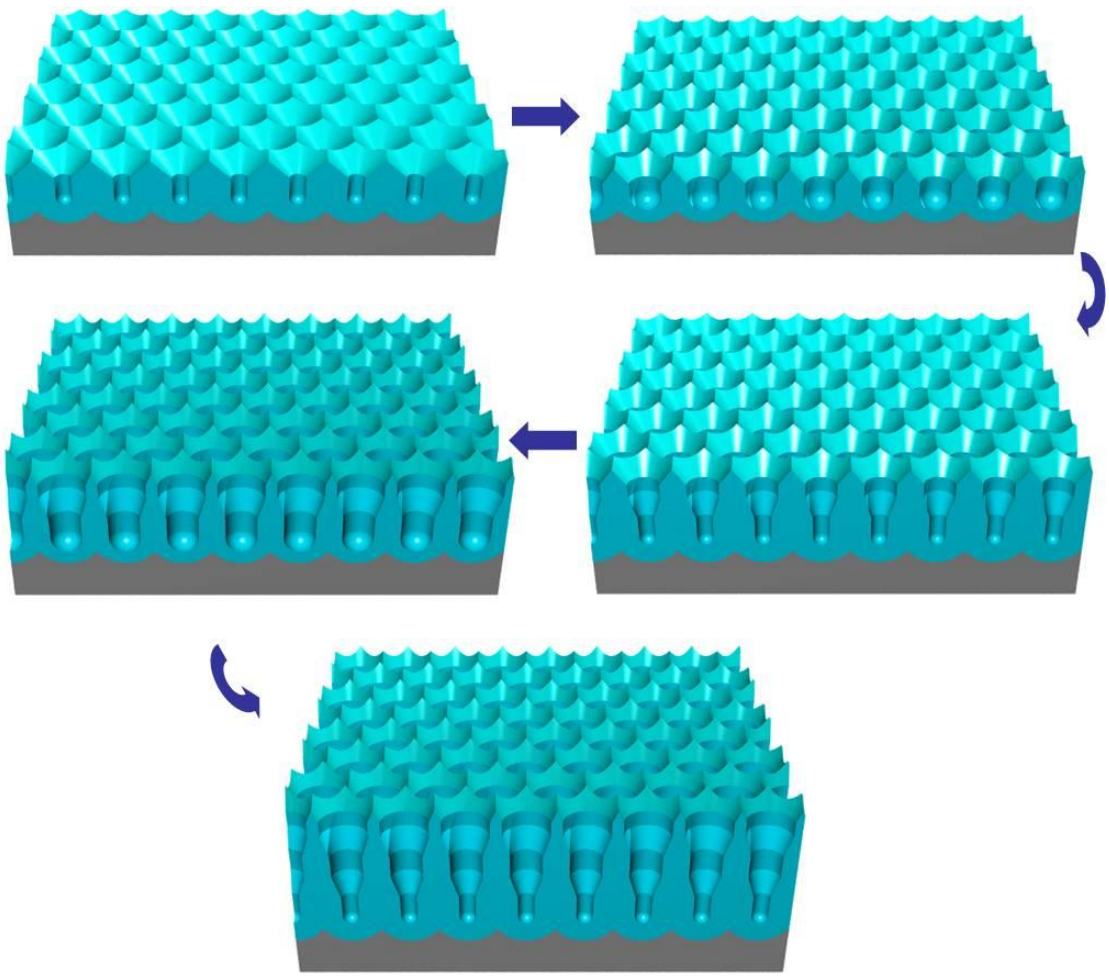

Figure S4. Schematic four-step anodization process for tri-diameter AAM, drawing from 2nd anodization.

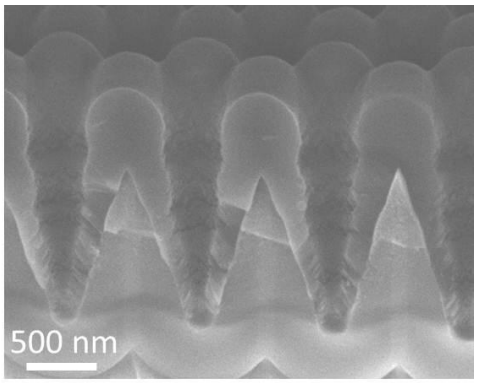

Figure S5. Cross-sectional view SEM image of a-Si nanocones embedded in AAM.